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Sheet 1 of 3

Substitute Form PTO-1449 (Modified)  <b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. <b>18239-023US1</b>	Application No. <b>10/597,806</b>
	Applicant <b>Bernhard Kneer et al.</b>		
	Filing Date <b>August 8, 2006</b>	Group Art Unit <b>3722</b>	

### U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	2005/0248856	11/2005	Omura et al.			
	AB	2003/174408	9/8/2003	Rostalski Hans-Juergen et al.			
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ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /M.A./

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							Yes	No
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	AYY	DD 224448	7/3/1985	Germany				

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Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AZZ	EP 1420302	5/19/2004	EPO				
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	AJJJ	Dammel et al., "193 nm Immersion Lithography - Taking the Plunge", Journal of Photopolymer Science and Technology, vol. 17 no. 4, pp 587-607 (2004).
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	AMMM	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, New York, NY, Vol. 17, No. 6, November 1999 (199-11) pp 3306-3309.
	ANNN	Smith, Bruce, "Water-based 193nm Immersion Lithography", Online!, <a href="http://www.semtech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf">http://www.semtech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf</a> , (January 28, 2004).

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